Thin Solid Films, *185* (1990) 375–377

Contents of Vol. 185

Issue 1

Electronics and Optics

On the temperature dependence of the intergrain barriers in polycrystalline CdS thin films 1
İ. Günal and H. Mamikoglu (Ankara, Turkey)

Investigation of chemically vapour deposited tungsten and tungsten silicide as contacts to n^+ and p^+ silicon areas 9
M. Hammar, S.-L. Zhang, R. Buchta and T. Johansson (Kista, Sweden)

Metallurgical and Protective Layers

Adhesion studies of magnetron-sputtered copper films on nickel substrates: effects of substrate surface pretreatments 21
G. H. Lee, M. Cailler (Nantes, France) and S. C. Kwon (Kyung-Nam, South Korea)

Adhesion studies of magnetron-sputtered copper films on Inconel substrates: effects of substrate surface pretreatments 35
G. H. Lee, M. Cailler (Nantes, France) and S. C. Kwon (Kyung-Nam, South Korea)

Relaxation de contrainte dans un dépôt fissuré. 57
A Mezin, J.-P. Chambard, J. Lepage and M. Nivoit (Nancy, France)

Preparation and Characterization

Sputtering characteristics of diamond and hydrogenated amorphous carbon films by r.f. plasma . 71
K. Kobayashi, K. Yamamoto, N. Mutsukura and Y. Machi (Tokyo, Japan)

Sputtering-induced surface roughness of metallic thin films 79
D. Marton and J. Fine (Gaithersburg, MD, U.S.A.)

Critical temperature for the formation of solid amorphous films 91
I. Avramov (Sofia, Bulgaria), S. Grudeva (Russe, Bulgaria) and I. Gutzow (Sofia, Bulgaria)

Properties of two-phase cadmium stannate thin films. 97
J. M. Blackmore and A. F. Cattell (Great Malvern, U.K.)

Synthesis of diamond thin films by hot-filament-assisted chemical vapour deposition 111
A. M. Bonnot (Grenoble, France)

Compositional studies of various metal oxide coatings on glass 123
O. B. Ajayi, M. S. Akanni, J. N. Lambi (Ile-Ife, Nigeria), C. Jeynes and J. F. Watts (Guildford, U.K.)

Sputter-deposited SiO_x films for liquid crystal alignment 137
T. Motohiro and Y. Taga (Aichi-ken, Japan)

Correlations between sputtering parameters, composition and resistivity of granular NbN films . . 145
R. Cabanel, J. Chaussy, J. Geneste, J. Mazuer and J. C. Villegier (Grenoble, France)

Growth behaviour and superconductivity of BiSrCaCuO films on MgO(100) substrates 159
W. T. Lin, H. C. Chu, Y. L. Chu, H. S. Lin, Y. K. Fang, C. Y. Chang (Tainan, Taiwan), P. T. Wu and J. H. Kung (Hsinchu, Taiwan)

Physicochemical characterization of covalently bonded alkyl monolayers on silica surfaces 169
Y. Duvault, A. Gagnaire, F. Gardies, N. Jaffrezic-Renault, C. Martelet (Ecully, France), D. Morel, J. Serpinet (Villeurbanne, France) and J.-L. Duvault (Ecully, France)

TiO_2-loaded Nafion membranes: an electron microscope investigation 181
A. Albu-Yaron, L. Arcan (Bet Dagan, Israel) and C. Heitner-Wirguin (Jersualem, Israel)

Langmuir–Blodgett and Related Films

Anisotropy of thermal expansion of thin polyimide films 189
G. Elsner, J. Kempf, J. W. Bartha and H. H. Wagner (Sindelfingen, F.R.G.)

Issue 2

Metallurgical and Protective Layers

The structure of thin films deposited from a sintered tungsten carbide with a high cobalt content (15 wt.%) 199
A. Cavaleiro, M. T. Vieira (Coimbra, Portugal) and G. Lempériere (Nantes, France)

The morphology and orientation of Cr–N films deposited by reactive ion plating 219
D. D. Wang and T. Oki (Nagoya, Japan)

Preparation and Characterization

Infrared and Raman spectra of reactively sputtered amorphous GeN_x–H film 231
G. Chen and F. Zhang (Lanzhou, China)

Thermodynamic investigation of selective molybdenum chemical vapour deposition: influence of growth conditions and gas additives on the selectivity of the process 235
A. Hårsta and J.-O. Carlsson (Uppsala, Sweden)

Deposition of carbon films by bias magnetron sputtering in neon and argon 247
I. Petrov, I. Ivanov, V. Orlinov, J. Kourtev and J. Jelev (Sofia, Bulgaria)

Characteristics of neutralized indium tin oxide–polycrystalline silicon 257
M. Mudrik, S. Eliahou and N. Croitoru (Ramat Aviv, Israel)

Spray pyrolysis electrochromic WO_3 films: electrical and X-ray diffraction measurements 265
J. Zhang, S. A. Wessel and K. Colbow (Burnaby, British Columbia, Canada)

Thin film thickness measurement using the energy-dispersive spectroscopy technique in a scanning electron microscope 279
R. Pascual (Kingston, Ontario, Canada), L. R. Cruz, C. L. Ferreira and D. T. Gomes (Rio de Janeiro, Brazil)

Langmuir–Blodgett and Related Films

Preparation of surfactant multilayer films on solid substrates by deposition from organic solution
M. Seul and M. J. Sammon (Murray Hill, NJ, U.S.A.) 287

Laser-induced geometrical change of fluorescent traps in cast thin films of ω-(1-pyrenyl) alkanoic acids 307
A. Itaya, T. Kawamura, H. Masuhara (Kyoto, Japan) and Y. Taniguchi (Tokyo, Japan)

Device applications of Langmuir–Blodgett films: electrophotographic photoreceptors incorporating multilayers of fluorenylidene and carbazole-containing surfactants as charge-blocking elements 321
J. W. Taylor, D. A. Holden (Kingston, Ontario, Canada), G. J. Kovacs and R. O. Loutfy (Mississauga, Ontario, Canada)

Real-time microfluorescence studies of Langmuir–Blodgett deposition: monolayer adsorption and desorption 335
H. Riegler (Mainz, F.R.G.) and J. D. LeGrange (Princeton, NJ, U.S.A.)

Condensed Matter Film Behaviour

The influence of iron on properties of deposited Ni–Cr–Si film resistors 341
F. B. Chang and L. N. Kang (Xi'an, China)

On the breakdown statistics of very thin SiO_2 films 347
J. Suñé, I. Placencia, N. Barniol, E. Farrés, F. Martín and X. Aymerich (Barcelona, Spain)

Effect of borophosphosilicate film post-growth treatments on the flow angle 363
Y. H. Tsai, S. L. Hsu, F. C. Tseng and C. S. Yoo, (Hsin-Chu, Taiwan)

Corrigendum 373

Author Index 374